

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-25 (Canceled).

Claim 26 (Previously Presented): A vapor deposition material comprising a polycrystalline body, a sintered body, or single crystal having a surface covered with a fluoride layer, wherein the fluoride layer comprises a material of formula



wherein M is Mg, Ca, Sr, Ba, an alkali earth compound metal, a rare earth metal, or a compound metal of an alkali earth metal and rare earth metal, and  $0 < X < 2$  and  $0 < Y \leq 4$ .

Claims 27-28 (Canceled).

Claim 29 (Previously Presented): An FPD obtained by vapor depositing the vapor deposition material according to claim 26 onto a substrate.

Claim 30 (Previously Presented): The vapor deposition material according to Claim 26, wherein the fluoride layer is from 0.1 nm to 100  $\mu$ m in thickness.

Claim 31 (Previously Presented): The vapor deposition material according to Claim 26, wherein the fluoride layer is from 1 nm to 1  $\mu$ m in thickness.

Claim 32 (Previously Presented): The vapor deposition material of Claim 26, wherein the entire surface of the polycrystalline body, sintered body, or single crystal is covered with a fluoride layer.

Claim 33 (Previously Presented): The vapor deposition material of Claim 26, comprising a polycrystalline body covered with a fluoride layer.

Claim 34 (Previously Presented): The vapor deposition material of Claim 26, comprising a sintered body covered with a fluoride layer.

Claim 35 (Previously Presented): The vapor deposition material of Claim 26, comprising a single crystal covered with a fluoride layer.

Claim 36 (Previously Presented): The vapor deposition material of Claim 26, wherein  $0.25 \leq X < 2$ .

Claim 37 (Previously Presented): The vapor deposition material of Claim 26, wherein  $0.5 \leq X < 2$ .

Claim 38 (Previously Presented): The vapor deposition material of Claim 26, wherein  $1 \leq Y \leq 4$ .

Claim 39 (Previously Presented): The vapor deposition material of Claim 26, wherein the fluoride layer is a material selected from the group consisting of  $MO_{0.5}F$ ,  $MO_{0.25}F_{1.25}$ ,  $MOF_2$ ,  $MOF$ , and  $MOF_{0.66}$ .

Claim 40 (Previously Presented): The vapor deposition material of Claim 26, wherein the polycrystalline body, sintered body or single crystal is free of a substrate.